

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
1	BRS	L1	14	"6162737"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 12:31		
2	BRS	L2	2	"20040110377"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 13:26		
3	BRS	L3	149	"5286344"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:42		
4	BRS	L4	9665	(buffer or "silicon oxide" or oxide) same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemcial vapor deposition"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:49		
5	BRS	L5	5197	4 and (self align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:50		
6	BRS	L6	3761	5 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:52		
7	BRS	L7	7934	(buffer or "silicon oxide" or oxide) same layer same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemcial vapor deposition"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:52		
8	BRS	L8	4310	7 and (self align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:53		

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9	BRS	L9	3164	8 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:53		
10	BRS	L10	2108	(buffer or "silcon oxide" or oxide) same layer same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemcial vapor deposition")) same semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:56		
11	BRS	L11	1014	10 and (self align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:57		
12	BRS	L12	751	11 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 14:57		
13	BRS	L13	648	(buffer or "silcon oxide" or oxide) same layer same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemcial vapor deposition")) same temperature same semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:27		
14	BRS	L14	295	13 and (self align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:28		
15	BRS	L15	211	14 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:28		
16	BRS	L16	7934	(buffer or "silcon oxide" or oxide) same layer same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemcial vapor deposition"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:52		

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
17	BRS	L17	2753	(buffer or "silicon oxide" or oxide) same layer same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemical vapor deposition")) same temperature	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:53		
18	BRS	L18	551	16 same (self align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 16:31		
19	BRS	L19	447	18 and @pd<="20031114"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:29		
20	BRS	L20	48383 9	(buffer or "silicon oxide" or oxide) same layer same (MTO or (mid temperature oxide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:52		
21	BRS	L21	861	(buffer or "silicon oxide" or oxide) same (MTO or ("mid temperature oxide"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:52		
22	BRS	L22	3354	(buffer or "silicon oxide" or oxide) same (MTO or (mid temperature oxide)) same (lpcvd or ("low pressure chemical vapor deposition")) same temperature	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 15:53		
23	BRS	L23	26	(buffer or "silicon oxide" or oxide) same (MTO or ("mid temperature oxide")) same (lpcvd or ("low pressure chemical vapor deposition")) same temperature	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 16:28		
24	BRS	L24	1468	(remov\$3 or clean\$3 or etch\$3) same (buffer or "silicon oxide" or oxide) same (("ammonium hydroxide" or "NH.sub.4OH" or NH4OH) and (peroxide or H2O2 or "H.sub.2O.sub.2") and (water or DI orH2O or "H.sub.2O"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 16:31		

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25	BRS	L25	16	(remov\$3 or clean\$3 or etch\$3) same (buffer or "silicon oxide" or oxide) same ("ammonium hydroxide" or "NH.sub.4OH" or NH4OH) and (peroxide or H2O2 or "H.sub.2O.sub.2") and (water or DI orH2O or "H.sub.2O") same (self adj align\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/11/08 16:32		